

	Hits	Search Text	DBs
9	0	((resist or photoresist) same (first or initial or interference or holograph\$4)) and (((second or plural\$3 or multiple) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3 or (arbitrary near5 irregularit\$3))) and ((design near5 layout) same (mask\$4 near9 layout) same (remainder or layout or pattern) same ((expans\$5 or resiz\$5 or expand\$4) near22 (perpendicular or angle)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
10	0	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3 or (arbitrary near5 irregularity))) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((design near5 layout) same (mask\$4 near9 layout) same (remainder or layout or pattern) same ((expans\$5 or resiz\$5 or expand\$4) near22 (perpendicular or angle)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	0	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3 or (arbitrary near5 irregularity))) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((design near5 layout) same (mask\$4 near9 layout) same ((expans\$5 or resiz\$5 or expand\$4) near22 (perpendicular or angle)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
12	0	((resist or photoresist) same (first or initial or interference or holograph\$4) same (expos\$4 or irradiat\$4 or illuminat\$4)) and (((additional or different or another or second) near14 (expos\$4 or irradiat\$4 or illuminat\$4)) same (mask or photomask or reticle or optical or (direct near9 writ\$4) or maskless or blanket) same (break\$3 or non\$4contiguous or continuity or bridg\$4 or connect\$4 or interconnect\$3 or (arbitrary near5 irregularity))) and pitch\$4 and (linewidth or LW) and ((imprint\$4 or (electron near3 beam) or e\$3beam or ion\$3beam) near7 (system or module or apparatus or imping\$4)) and ((design near5 layout) same (mask\$4 near9 layout) same (expans\$5 or resiz\$5 or expand\$4))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB